

### **Abstract of the Disclosure**

A method of forming a film on a substrate using Group IVB, VB, or VIB metal complexes. The methods are particularly suitable for the preparation of semiconductor structures using chemical vapor deposition techniques and systems.

DATE OF DEPOSIT 25 May 2001  
I HEREBY CERTIFY THAT THIS PAPER OR FEE IS BEING DEPOSITED WITH THE  
UNITED STATES POSTAL SERVICE "EXPRESS-MAIL POST OFFICE TO ADDRESSEE"  
SERVICE UNDER 37 CFR 1.10 ON THE DATE INDICATED ABOVE AND IS ADDRESSED TO  
THE ASSISTANT COMMISSIONER FOR PATENTS  
WASHINGTON, D C 20231

PRINTED NAME JACQUELYN K TORBORG  
SIGNATURE Jacquelyn K. Torborg